L Number	Hits	Search Text	DB	Time stamp
-	100	(etch\$3 with (silicon adj nitride Si3N4	USPAT;	2004/03/20 13:26
ļ		"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?	US-PGPUB;	
		adj N?sub.?)) same (Cu copper) and ((oxygen	EPO; JPO;	
		O2 "O.sub.2") same (hydrofluorocaron CHF	DERWENT;	
		CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3	IBM_TDB	
	20	F" "CHF.sub.3")) (etch\$3 with (silicon adj nitride Si3N4	USPAT;	2003/01/10 16:39
-	22	"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?	US-PGPUB;	2000, 02, 21
i		adj N?sub.?)) same (Cu copper) same (oxygen	EPO; JPO;	
		O2 "O.sub.2") same (bydrofluorocarbon	DERWENT;	
		hydrofluoromethane \$3fluoromethane methane	IBM TDB	
		adj \$3fluoride CHF CH2F2 CH3F CHF3 "CH.sub.2	_	
		F.sub.2" "CH.sub.3 F" "CHF.sub.3")		
_	8	(etch\$3 with (silicon adj nitride Si3N4	USPAT;	2003/01/17 13:58
		"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?	US-PGPUB;	
		adj N?sub.?) WITH (oxygen 02 "O.sub.2") WITH	EPO; JPO;	
		(hydrofluorocaron CHF CH2F2 CH3F CHF3	DERWENT;	
		"CH.sub.2 F.sub.2" "CH.sub.3 F"	IBM_TDB	
		"CHF.sub.3")) same (Cu copper)	**************************************	2002/01/17 14:00
_	5	(etch\$3 with (silicon adj nitride Si3N4	USPAT;	2003/01/17 14:00
		"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?	US-PGPUB;	
		adj N?sub.?)) same (Cu copper) and ((oxygen	EPO; JPO; DERWENT;	
		02 "0.sub.2") same (hydrofluoroMETHANE	IBM TDB	
		METHYLENE\$3FLUORIDE \$4FLUOROMETHANE methane	100-100	
	1.0	adj \$3fluoride)) ((etch\$3 with (silicon adj nitride Si3N4	USPAT;	2003/01/17 14:00
-	13	"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?	US-PGPUB;	
		adj N?sub.?) WITH (oxygen O2 "O.sub.2") WITH	EPO; JPO;	
		(hydrofluorocaron CHF CH2F2 CH3F CHF3	DERWENT;	
		"CH.sub.2 F.sub.2" "CH.sub.3 F"	IBM TDB	
1		"CHF.sub.3")) same (Cu copper)) ((etch\$3	_	
		with (silicon adj nitride Si3N4 "Si.sub.3		
		N.sub.4" SiN "SiN.sub.x" Si?sub.? adj		
		N?sub.?)) same (Cu copper) and ((oxygen O2		
		"O.sub.2") same (hydrofluoroMETHANE		
		METHYLENE\$3FLUORIDE \$4FLUOROMETHANE methane		
		adj \$3fluoride)))		2002/02/15 11 52
-	67	(etch\$3 with (silicon adj nitride Si3N4	USPAT;	2003/03/17 11:52
		"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?	US-PGPUB;	
		adj N?sub.?)) same (Cu copper) and ((oxygen	EPO; JPO;	
		02 "0.sub.2") same (hydrofluorocarbon	DERWENT; IBM TDB	
		fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H	1BM_IDB	
		CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H"		
		"CFH.sub.3") same (inert He Ne Ar Xe helium		
		neon argon xenon))		
	55		USPAT;	2003/03/17 11:53
_	33	"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?	US-PGPUB;	
		adj N?sub.?)) same (Cu copper) and ((oxygen	EPO; JPO;	
		02 "O.sub.2") same (hydrofluorocarbon	DERWENT;	
		fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2	IBM_TDB	
		F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H		
		CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H"		
		"CFH.sub.3") same (inert He Ne Ar Xe helium		
		neon argon xenon))) and ((oxygen O2		
		"O.sub.2") with (hydrofluorocarbon		
		fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2		
		F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H		
	1	CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H"		
		"CFH.sub.3") with (inert He Ne Ar Xe helium		
Í		neon argon xenon))		

_	22	(((etch\$3 with (silicon adj nitride Si3N4	USPAT;	2003/03/17 11:57
1		"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?	US-PGPUB;	
		adj N?sub.?)) same (Cu copper) and ((oxygen	EPO; JPO;	
		02 "0.sub.2") same (hydrofluorocarbon	DERWENT;	
		fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2	IBM TDB	
		F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H	_	
		CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H"		
		"CFH.sub.3") same (inert He Ne Ar Xe helium		
		neon argon xenon))) and ((oxygen 02		·
		"O.sub.2") with (hydrofluorocarbon		
		fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2		
		Illuorocarpon CHF CH2F2 CH3F CHF3 CH. Sub. 2		
1		F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H		
		CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H"		
		"CFH.sub.3") with (inert He Ne Ar Xe helium		
		neon argon xenon))) and ((oxygen O2	1	
		"O.sub.2") near2 (hydrofluorocarbon		
		fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2		
		F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H		
		CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H"		
		"CFH.sub.3") near2 (inert He Ne Ar Xe helium		
		neon argon xenon))		
_	6	((((etch\$3 with (silicon adj nitride Si3N4	USPAT;	2003/03/17 11:56
		"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?	US-PGPUB;	
		adj N?sub.?)) same (Cu copper) and ((oxygen	EPO; JPO;	
1		02 "O.sub.2") same (hydrofluorocarbon	DERWENT;	
		fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2	IBM TDB	1
		F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H	_	
		CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H"		
		"CFH.sub.3") same (inert He Ne Ar Xe helium		
		neon argon xenon))) and ((oxygen O2		
		"O.sub.2") with (hydrofluorocarbon		1
		fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2		
	Į	F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H		
		CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H"		
		"CFH.sub.3") with (inert He Ne Ar Xe helium		
		"Crn. sub.5") with (there he he he herium		
		neon argon xenon))) and ((oxygen O2		
		"O.sub.2") near2 (hydrofluorocarbon	1	
		fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2		
		F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H		
1		CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H"		
		"CFH.sub.3") near2 (inert He Ne Ar Xe helium		
		neon argon xenon))) and ((oxygen 02		
		"O.sub.2") near (hydrofluorocarbon		
		fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2		
		F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H		
		CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H"		
		"CFH.sub.3") near (inert He Ne Ar Xe helium		
		neon argon xenon))		

- 16	(((etch\$3 with (silicon adj nitride Si3N4	USPAT;	2003/03/17 12:02
	"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?	US-PGPUB;	
	adj N?sub.?)) same (Cu copper) and ((oxygen	EPO; JPO;	
	02 "O.sub.2") same (hydrofluorocarbon	DERWENT;	
	fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2	IBM_TDB	
	F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H		
	CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H"		
	"CFH.sub.3") same (inert He Ne Ar Xe helium		
	neon argon xenon))) and ((oxygen O2	1	
	"O.sub.2") with (hydrofluorocarbon		
	fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2		
	F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H		
	CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H"		
	"CFH.sub.3") with (inert He Ne Ar Xe helium		
	neon argon xenon))) and ((oxygen O2		
	"O.sub.2") near2 (hydrofluorocarbon		1
	fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2		
}	F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H		
	CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H"		
	"CFH.sub.3") near2 (inert He Ne Ar Xe helium		
	neon argon xenon))) not ((((etch\$3 with		
	(silicon adj nitride Si3N4 "Si.sub.3		
	N.sub.4" SiN "SiN.sub.x" Si?sub.? adj		
·	N?sub.?)) same (Cu copper) and ((oxygen O2		
	"O.sub.2") same (hydrofluorocarbon		
	fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2		
	F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H		
	CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H"		
	"CFH.sub.3") same (inert He Ne Ar Xe helium		
	neon argon xenon))) and ((oxygen O2	İ	
	"O.sub.2") with (hydrofluorocarbon		
	fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2		
	F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H		
	CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H"	ĺ	
	"CFH.sub.3") with (inert He Ne Ar Xe helium	1	·
	neon argon xenon))) and ((oxygen O2		
	"O.sub.2") near2 (hydrofluorocarbon		
	fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2		
	F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H		
	CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H"		
	"CFH.sub.3") near2 (inert He Ne Ar Xe helium		
	neon argon xenon))) and ((oxygen O2	1	
	"O.sub.2") near (hydrofluorocarbon		
	fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2		
	F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H		
	CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H"	1	
	"CFH.sub.3") near (inert He Ne Ar Xe helium		
	neon argon xenon)))	L	

[-	33	(((etch\$3 with (silicon adj nitride Si3N4	USPAT;	2003/03/17 12:13
		"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?	US-PGPUB; EPO; JPO;	
		adj N?sub.?)) same (Cu copper) and ((oxygen O2 "O.sub.2") same (hydrofluorocarbon	DERWENT;	
		fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2	IBM_TDB	
		F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H	_	
	İ	CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H"		
		"CFH.sub.3") same (inert He Ne Ar Xe helium		
		neon argon xenon))) and ((oxygen O2		
		"O.sub.2") with (hydrofluorocarbon fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2		
		F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H		
		CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H"		
]		"CFH.sub.3") with (inert He Ne Ar Xe helium		
		neon argon xenon))) not (((etch\$3 with		
		(silicon adj nitride Si3N4 "Si.sub.3		
ļ		N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?)) same (Cu copper) and ((oxygen O2		
İ		"O.sub.2") same (tu copper) and (toxygen of		
		fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2		
	1	F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H		
		CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H"		
		"CFH.sub.3") same (inert He Ne Ar Xe helium		
	1	neon argon xenon))) and ((oxygen O2 "O.sub.2") with (hydrofluorocarbon		
	ļ -	fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2		
		F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H		
		CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H"		
		"CFH.sub.3") with (inert He Ne Ar Xe helium		
		neon argon xenon))) and ((oxygen O2		
		"O.sub.2") near2 (hydrofluorocarbon fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2		
		F. sub.2" "CH. sub.3 F" "CHF. sub.3" CF2H2 CF3H		
1		CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H"		
		"CFH.sub.3") near2 (inert He Ne Ar Xe helium		
		neon argon xenon)))	параш.	2002/02/17 12:21
_	0	((etch\$3 with (silicon adj nitride Si3N4	USPAT; US-PGPUB;	2003/03/17 12:21
		"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?)) same (Cu copper) and ((oxygen	EPO; JPO;	1
		02 "O.sub.2") same (hydrofluorocarbon	DERWENT;	
		fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2	IBM_TDB	
		F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H		
		CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H"		
		"CFH.sub.3") same (inert He Ne Ar Xe helium		
		neon argon xenon))) and etch\$3 same (ash\$3 (photoresist resist) remov\$3 strip\$4) same		
		((single same one) near chamber)		
_	0	((etch\$3 with (silicon adj nitride Si3N4	USPAT;	2003/03/17 12:21
	1	"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?	US-PGPUB;	
		adi N?sub.?)) same (Cu copper) and ((oxygen	EPO; JPO;	
		O2 "O.sub.2") same (hydrofluorocarbon fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2	DERWENT; IBM TDB	
		F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H	1	
		CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H"		
1		"CFH.sub.3") same (inert He Ne Ar Xe helium		
		neon argon xenon))) and ((single same one)		
1		near chamber)	USPAT;	2003/03/17 12:21
-	7	((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?	US-PGPUB;	2505/05/17 12.21
		adj N?sub.?)) same (Cu copper) and ((oxygen	EPO; JPO;	
		02 "O.sub.2") same (hydrofluorocarbon	DERWENT;	
		fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2	IBM_TDB	
		F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H		
		CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H"		
1		"CFH.sub.3") same (inert He Ne Ar Xe helium		
	1	neon argon xenon))) and ((single same one) with chamber)		
_	1408	1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1	USPAT;	2004/03/20 13:08
	1400	"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?	US-PGPUB;	
		adj N?sub.?) same (Cu copper)	EPO; JPO;	
			DERWENT;	
			IBM_TDB	

	6201	etch\$3 with (silicon adj nitride Si3N4	USPAT;	2004/03/20 13:11
		"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)	US-PGPUB; EPO; JPO; DERWENT;	
_	428	(etch\$3 with (silicon adj nitride Si3N4	IBM_TDB USPAT;	2004/03/20 13:13
		"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and etch\$3 same ((oxygen O2 "O.sub.2") with	US-PGPUB; EPO; JPO; DERWENT;	
		(hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F"	IBM_TDB	
-	115	"CHF.sub.3")) (etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?	USPAT; US-PGPUB;	2004/03/20 13:10
		adj N?sub.?) same (Cu copper)) and etch\$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3	EPO; JPO; DERWENT; IBM_TDB	
e-		"CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))		
-	1234	the transfer of mitraide GiaNA	USPAT; US-PGPUB; EPO; JPO;	2004/03/20 13:11
	·	adj N?sub.?) and (Cu copper) and (Silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu	DERWENT; IBM_TDB	
-	114	copper) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?	USPAT; US-PGPUB;	2004/03/20 13:12
		adj N?sub.?) and (Cu copper)) and etch\$3 same ((oxygen 02 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3	EPO; JPO; DERWENT; IBM TDB	
		"CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (silicon adj nitride	_	
	855	Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper) (etch\$3 with (silicon adj nitride Si3N4	USPAT;	2004/03/20 13:12
		"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN	US-PGPUB; EPO; JPO; DERWENT; IBM TDB	
	80	"SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper) ((etch\$3 with (silicon adj nitride Si3N4	USPAT;	2004/03/20 13:12
_		"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch\$3 same ((oxygen 02 "0.sub.2") with	US-PGPUB; EPO; JPO; DERWENT;	
		(hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F"	IBM_TDB	
		"CHF.sub.3"))) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)		
-	179	(etch\$3 with (silicon adj nitride Si3N4 "Si sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?	USPAT; US-PGPUB; EPO; JPO;	2004/03/20 13:16
		adj N?sub.?) and (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3	DERWENT; IBM_TDB	
-	52	"Si sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?	USPAT; US-PGPUB;	2004/03/20 13:17
	ļ	adj N?sub.?) same (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3	EPO; JPO; DERWENT; IBM_TDB	
_	38	corrosion) ((etch\$3 with (silicon adj nitride Si3N4	USPAT; US-PGPUB;	2004/03/20 13:19
		"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN	EPO; JPO; DERWENT;	
		"SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3)	IBM_TDB	
		with (oxidation oxidiz\$3 corrosion)		

				122122
-	47	((etch\$3 with (silicon adj nitride Si3N4	USPAT;	2004/03/20 13:19
		"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?	US-PGPUB;	
		adj N?sub.?) and (Cu copper)) and (silicon	EPO; JPO;	
		adi nitride Si3N4 "Si.sub.3 N.sub.4" SiN	DERWENT;	
		"SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu	IBM_TDB	
		copper)) and (oxygen O2 "O.sub.2") with	_	
		(suppress\$3 inhibit\$3 prevent\$3 reduce\$3)		
		with (oxidation oxidiz\$3 corrosion)		
	205	1	USPAT;	2004/03/20 13:21
-	205	"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?	US-PGPUB;	
1		adj N?sub.?) same (Cu copper)) and etch\$3	EPO; JPO;	
		same ((oxygen 02 "O.sub.2") with	DERWENT;	
		(hydrofluorocaron CHF CH2F2 CH3F CHF3	IBM TDB	
		(nydroffuorocaton CHF CH2F2 CH3F CHF3	1511_155	
		"CH.sub.2 F.sub.2" "CH.sub.3 F"		
		"CHF.sub.3"))) (((etch\$3 with (silicon adj		
		nitride Si3N4 "Si.sub.3 N.sub.4" SiN		
		"SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu		
		copper)) and etch\$3 same ((oxygen 02		
		"O.sub.2") with (hydrofluorocaron CHF CH2F2		
		CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F"		i
1		"CHF.sub.3"))) and (silicon adj nitride		·
		Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x"		
		Si?sub.? adj N?sub.?) with (Cu copper))	1	<u> </u>
		(((etch\$3 with (silicon adj nitride Si3N4		
		"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?		
		adj N?sub.?) same (Cu copper)) and etch\$3		
}		same ((oxygen 02 "0.sub.2") with		
		(hydrofluorocaron CHF CH2F2 CH3F CHF3		
1		"CH.sub.2 F.sub.2" "CH.sub.3 F"		1
		"CHF.sub.3"))) and (silicon adj nitride		}
		Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x"		
		Si?sub.? adj N?sub.?) with (Cu copper))		1
		((etch\$3 with (silicon adj nitride Si3N4		
		"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?		
		"S1.Sub.3 N.Sub.4" SIN "SIN.Sub.X S1:Sub.:		
		adj N?sub.?) same (Cu copper)) and (oxygen		
		O2 "O.sub.2") with (suppress\$3 inhibit\$3		
		prevent\$3 reduce\$3) with (oxidation oxidiz\$3		
1		corrosion)) (((etch\$3 with (silicon adj		
		nitride Si3N4 "Si.sub.3 N.sub.4" SiN		
		"SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu		
		copper)) and etch\$3 same ((oxygen O2		1
		"O.sub.2") with (hydrofluorocaron CHF CH2F2		
		CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F"		
		"CHF.sub.3"))) and (oxygen 02 "0.sub.2")		
		with (suppress\$3 inhibit\$3 prevent\$3		
		reduce\$3) with (oxidation oxidiz\$3		
		corrosion)) (((etch\$3 with (silicon adj		
		nitride Si3N4 "Si.sub.3 N.sub.4" SiN		
		"SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu		
		copper)) and (silicon adj nitride Si3N4		
		"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?		
		adj N?sub.?) with (Cu copper)) and (oxygen		
		O2 "O.sub.2") with (suppress\$3 inhibit\$3		
		prevent\$3 reduce\$3) with (oxidation oxidiz\$3		
		corrosion)) (((etch\$3 with (silicon adj		
		nitride Si3N4 "Si.sub.3 N.sub.4" SiN		
		"SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu	1	
		"SIN.SUD.X" SI:SUD.: duj N:SUD.: daiu (Cu		
		copper)) and (silicon adj nitride Si3N4		
1		"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?		
		adj N?sub.?) with (Cu copper)) and (oxygen		
	1	O2 "O.sub.2") with (suppress\$3 inhibit\$3		
		prevent\$3 reduce\$3) with (oxidation oxidiz\$3		
		corrosion))	<u> </u>	<u> </u>

	323	(((etch\$3 with (silicon adj nitride Si3N4	USPAT;	2004/03/20 13:21
_	323	"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?	US-PGPUB;	
		adj N?sub.?) same (Cu copper)) and etch\$3	EPO; JPO;	
		same ((oxygen 02 "O.sub.2") with	DERWENT;	
		(hydrofluorocaron CHF CH2F2 CH3F CHF3	IBM_TDB	
		"GIT 2 E cub 2" "CU cub 3 E"		
1		"CH.sub.2 F.sub.2" "CH.sub.3 F"		
		"CHF.sub.3"))) (((etch\$3 with (silicon adj		
1		nitride Si3N4 "Si.sub.3 N.sub.4" SiN		
		"SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu		
	!	copper)) and etch\$3 same ((oxygen 02		
		"O.sub.2") with (hydrofluorocaron CHF CH2F2		
		CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F"		
		"CHF.sub.3"))) and (silicon adj nitride		
		Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x"		į
		Si?sub.? adj N?sub.?) with (Cu copper))		
		(((etch\$3 with (silicon adj nitride Si3N4		1
		"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?]
		"S1.Sub.3 N.Sub.4" SIN "SIN.Sub.k SI.Sub		
		adj N?sub.?) same (Cu copper)) and etch\$3		
		same ((oxygen 02 "0.sub.2") with		1
1		(hydrofluorocaron CHF CH2F2 CH3F CHF3		1
		"CH.sub.2 F.sub.2" "CH.sub.3 F"		
		"CHF.sub.3"))) and (silicon adj nitride		
		Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x"		
		Si?sub.? adj N?sub.?) with (Cu copper))		
		((etch\$3 with (silicon adj nitride Si3N4		
		"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?		
1		adj N?sub.?) same (Cu copper)) and (oxygen	1	
		O2 "O.sub.2") with (suppress\$3 inhibit\$3		
		prevent\$3 reduce\$3) with (oxidation oxidiz\$3		
		prevents3 reduces3) with (oxidation oxidizes		
		corrosion)) (((etch\$3 with (silicon adj		
		nitride Si3N4 "Si.sub.3 N.sub.4" SiN		
		"SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu		
		copper)) and etch\$3 same ((oxygen O2		
		"O.sub.2") with (hydrofluorocaron CHF CH2F2		
		CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F"		
		"CHF.sub.3"))) and (oxygen 02 "0.sub.2")		
		with (suppress\$3 inhibit\$3 prevent\$3		
		reduce\$3) with (oxidation oxidiz\$3		
		corrosion)) (((etch\$3 with (silicon adj		
		corrosion)) ((lecchiss with (silicon da)		
		nitride Si3N4 "Si.sub.3 N.sub.4" SiN		
		"SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu		
		copper)) and (silicon adj nitride Si3N4		
		"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?		
		adj N?sub.?) with (Cu copper)) and (oxygen		
		02 "O.sub.2") with (suppress\$3 inhibit\$3		
		prevent\$3 reduce\$3) with (oxidation oxidiz\$3		
		corrosion)) (((etch\$3 with (silicon adj		
		nitride Si3N4 "Si.sub.3 N.sub.4" SiN	1	1
1		"SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu		
		copper)) and (silicon adj nitride Si3N4	1	
		"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?		
		adj N?sub.?) with (Cu copper)) and (oxygen		
		auj Nrsub. () with (cu copper) and (oxygen		
		O2 "O.sub.2") with (suppress\$3 inhibit\$3		
		prevent\$3 reduce\$3) with (oxidation oxidiz\$3		1
1		corrosion))) ((etch\$3 with (silicon adj		1
	1	nitride Si3N4 "Si.sub.3 N.sub.4" SiN		[
		"SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu		
		copper)) and (oxygen 02 "0.sub.2") with		
		(suppress\$3 inhibit\$3 prevent\$3 reduce\$3)		
		with (oxidation oxidiz\$3 corrosion))		
_	4	1 /	USPAT;	2004/03/20 13:21
-		"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?	US-PGPUB;	
		adj N?sub.?) same (Cu copper)) and etch\$3	EPO; JPO;	
	1	auj Nisub.:/ same (ou copper// and comps	DERWENT;	
		same ((oxygen 02 "0.sub.2") with	IBM TDB	
		(hydrofluorocaron CHF CH2F2 CH3F CHF3	1217-1213	
		"CH.sub.2 F.sub.2" "CH.sub.3 F"		
		"CHF.sub.3"))) and (oxygen O2 "O.sub.2")		
	1	with (suppress\$3 inhibit\$3 prevent\$3		
		reduce\$3) with (oxidation oxidiz\$3		
		corrosion)	<u></u>	

2004/03/20 13:31 ((((etch\$3 with (silicon adj nitride Si3N4 USPAT; "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? US-PGPUB; EPO; JPO; adj N?sub.?) same (Cu copper)) and etch\$3 DERWENT; same ((oxygen 02 "O.sub.2") with IBM TDB (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and etch\$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch\$3 same ((oxygen 02 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch\$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (oxygen 02 "0.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion))) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (oxygen 02 "0.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion))) and (etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper) with (oxygen 02 "O.sub.2") with (hydrofluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))

-	2	(etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3	USPAT; US-PGPUB; EPO; JPO; DERWENT;	2004/03/20	13:31
		N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper) with (oxygen O2 "O.sub.2") with (hydrofluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))	IBM_TDB		
-	2	(etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper) with (oxygen O2 "O.sub.2") with (hydrofluorocarbon CHF CH2F2	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/20	13:32
-	37	"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/20	13:41
		N?sub.?) same (Cu copper) same (oxygen O2 "O.sub.2") same (hydrofluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))			
-	2	("6033584").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/03/20	13:45
	7	6033584.URPN.	USPAT	2004/03/20	13:41
-	5	("5225034" "5354490" "5549786"	USPAT	2004/03/20	
-	887	"5840629" "5897379").PN. (etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (hydrogen H2 "H.sub.2") with (plasma discharge)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/03/20	13:46

123	((((etch\$3 with (silicon adj nitride Si3N4	USPAT;	2004/03/20 13:46
	"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?	US-PGPUB;	
	adj N?sub.?) same (Cu copper)) and etch\$3	EPO; JPO;	
	same ((oxygen 02 "O.sub.2") with	DERWENT;	
	(hydrofluorocaron CHF CH2F2 CH3F CHF3	IBM TDB	
	"CH.sub.2 F.sub.2" "CH.sub.3 F"	_	•
	"CHF.sub.3"))) (((etch\$3 with (silicon adj		
	nitride Si3N4 "Si.sub.3 N.sub.4" SiN		
	"SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu		
	copper)) and etch\$3 same ((oxygen O2		
	"O.sub.2") with (hydrofluorocaron CHF CH2F2		
	CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F"		
	"CHF.sub.3"))) and (silicon adj nitride		<u> </u>
	Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x"		1
	Si?sub.? adj N?sub.?) with (Cu copper))		1
	(((etch\$3 with (silicon adj nitride Si3N4		
	"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?		
	adj N?sub.?) same (Cu copper)) and etch\$3		
	same ((oxygen 02 "O.sub.2") with		
	(hydrofluorocaron CHF CH2F2 CH3F CHF3		
	"CH.sub.2 F.sub.2" "CH.sub.3 F"		
	"CHF.sub.3"))) and (silicon adj nitride		
	Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x"		
	Si?sub.? adj N?sub.?) with (Cu copper))		
	((etch\$3 with (silicon adj nitride Si3N4		
	"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?		
	adj N?sub.?) same (Cu copper)) and (oxygen		
	O2 "O.sub.2") with (suppress\$3 inhibit\$3		1
	prevent\$3 reduce\$3) with (oxidation oxidiz\$3		
	corrosion)) (((etch\$3 with (silicon adj		
	nitride Si3N4 "Si.sub.3 N.sub.4" SiN		1
	"SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu		
	copper)) and etch\$3 same ((oxygen O2		
	"O.sub.2") with (hydrofluorocaron CHF CH2F2		
	CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F"		l i
	"CHF.sub.3"))) and (oxygen 02 "0.sub.2")		
	with (suppress\$3 inhibit\$3 prevent\$3		
	reduce\$3) with (oxidation oxidiz\$3		į
	corrosion)) (((etch\$3 with (silicon adj		1
	nitride Si3N4 "Si.sub.3 N.sub.4" SiN		İ
	"SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu		
	copper)) and (silicon adj nitride Si3N4		
	"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?		
	adj N?sub.?) with (Cu copper)) and (oxygen		
	O2 "O.sub.2") with (suppress\$3 inhibit\$3		
	prevent\$3 reduce\$3) with (oxidation oxidiz\$3		
	corrosion)) (((etch\$3 with (silicon adj		
	nitride Si3N4 "Si.sub.3 N.sub.4" SiN		1
	"SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu		1
	copper)) and (silicon adj nitride Si3N4	1	
	"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?		
	adj N?sub.?) with (Cu copper)) and (oxygen	1	
	O2 "O.sub.2") with (suppress\$3 inhibit\$3		1
	prevent\$3 reduce\$3) with (oxidation oxidiz\$3	1	
		1	1
	corrosion))) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN	1	
	"SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu		1
	copper)) and (oxygen 02 "0.sub.2") with		
	(suppress\$3 inhibit\$3 prevent\$3 reduce\$3)		
	with (oxidation oxidiz\$3 corrosion))) and		
	(hydrogen H2 "H.sub.2") with (plasma discharge)		1
	uischaige/	J	1

75 (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch\$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu	20 13:47
adj N?sub.?) same (Cu copper)) and etch\$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu	
same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu	
(hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu	
"CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu	
"CHF.sub.3"))) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu	
nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu	
"SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu	
copper)) and etch\$3 same ((oxygen O2	
"O.sub.2") with (hydrofluorocaron CHF CH2F2	
CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F"	
"CHF.sub.3"))) and (silicon adj nitride	
Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x"	
Si?sub.? adj N?sub.?) with (Cu copper))	
(((etch\$3 with (silicon adj nitride Si3N4	
"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?	
adj N?sub.?) same (Cu copper)) and etch\$3	
same ((oxygen 02 "0.sub.2") with	
(hydrofluorocaron CHF CH2F2 CH3F CHF3	l
"CH.sub.2 F.sub.2" "CH.sub.3 F"	1
"CHF.sub.3"))) and (silicon adj nitride	
Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x"	
Si?sub.? adj N?sub.?) with (Cu copper))	
((etch\$3 with (silicon adj nitride Si3N4	
"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?	
adj N?sub.?) same (Cu copper)) and (oxygen	
O2 "O.sub.2") with (suppress\$3 inhibit\$3	
prevent\$3 reduce\$3) with (oxidation oxidiz\$3	
corrosion)) (((etch\$3 with (silicon adj	
nitride Si3N4 "Si.sub.3 N.sub.4" SiN	
"SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu	
copper)) and etch\$3 same ((oxygen O2	
"O.sub.2") with (hydrofluorocaron CHF CH2F2	
CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F"	
"CHF.sub.3"))) and (oxygen O2 "O.sub.2")	
with (suppress\$3 inhibit\$3 prevent\$3	
reduce\$3) with (oxidation oxidiz\$3	
corrosion)) (((etch\$3 with (silicon adj	
nitride Si3N4 "Si.sub.3 N.sub.4" SiN	
"SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu	
copper)) and (silicon adj nitride Si3N4	
"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?	
adj N?sub.?) with (Cu copper)) and (oxygen	
O2 "O.sub.2") with (suppress\$3 inhibit\$3	
prevent\$3 reduce\$3) with (oxidation oxidiz\$3	
corrosion)) (((etch\$3 with (silicon adj	
nitride Si3N4 "Si.sub.3 N.sub.4" SiN	
"SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu	
copper)) and (silicon adj nitride Si3N4	
"Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.?	
adj N?sub.?) with (Cu copper)) and (oxygen	
O2 "O.sub.2") with (suppress\$3 inhibit\$3	
prevent\$3 reduce\$3) with (oxidation oxidiz\$3	
corrosion))) and (hydrogen H2 "H.sub.2")	
with (plasma discharge)	

2004/03/20 13:48 USPAT; (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? US-PGPUB; adj N?sub.?) same (Cu copper)) and (oxygen EPO; JPO; DERWENT; O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 IBM TDB corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (oxygen 02 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) and (oxygen 02 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch\$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (oxygen 02 "0.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch\$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and etch\$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch\$3 same ((oxygen 02 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch\$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (oxygen 02 "0.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu 3 (silicon adj nitride Si3N4 'Si.sub.3 N.sub.4" Sin SiN sub.x" Si?sub.?

Search History

C:\APPS\EAST\Workspaces\hpsmries\ilq93(656opper)) and (oxygen

O2 "O.sub.2") with (suppress\$3 inhibit\$3

USPAT; 2004/03/20 13:48 (((etch\$3 with (silicon adj nitride Si3N4 US-PGPUB; "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (oxygen EPO; JPO; DERWENT; O2 "O.sub.2") with (suppress\$3 inhibit\$3 IBM TDB prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch\$3 same ((oxygen 02 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (oxygen 02 "0.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) ((((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch\$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and etch\$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch\$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch\$3 same ((oxygen 02 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (oxygen 02 "0.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (silicon adj nitride Si3N4 "Si sub.3 N. sub.4" SiN "SiN. sub.x" Si?sub.? 3/26/04 11:08:31 AM Page 13 adj N?sub.?) with (Cu copper)) and (oxygen C:\APPS\EAST\Workspaces\vio.sibrizeq\\violity\offprisss\$3 inhibit\$3

prevent\$3 reduce\$3) with (oxidation oxidiz\$3

Search History